CDocket No. 005918 USA/FPS/MMCS/APC

PATENT/OFFICIAL

6 1 1 2005 THE UNITED STATES PATENT AND TRADEMARK OFFICE

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SHANMUGASUNDRAM et al.

Serial No. 09/943,955

Group Art Unit: 1765

Filed: August 31, 2001

Examiner: Lynette T. Umez Eronini

For:

FEEDBACK CONTROL OF A CHEMICAL MECHANICAL POLISHING DEVICE

PROVIDING MANIPULATION OF REMOVAL RATE PROFILES

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the document listed on the attached form PTO-1449. It is respectfully requested that this document be expressly considered during the prosecution of this application, and that the document be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents do not constitute prior art under the United States law, Applicants reserve the right

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to present to the Office the relevant facts and law regarding the appropriate status of such document.

The Commissioner is authorized to charge any deficiency in any fees pursuant to 37 CFR § 1.17 associated with this communication and to credit any excess payment to Deposit Account No. 08-0219.

Respectfully submitted,

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Date: 9/11/05 Date: ____

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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.